Tool ID: 505 Tool Location: 122

# **Equipment Information Sheet**

## **JEOL 9500**

 Manager:
 Alan R. Bleier
 607-254-4931

 Backup:
 Roberto Panepucci
 607-254-4855

 Backup:
 John Treichler
 607-254-4949

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

#### **SAFETY**

No safety concerns during normal operation

#### **USAGE RESTRICTIONS**

No buddy system restrictions imposed on normal operation.

Please review electron beam lithography training materials, in AFS, at shares - public - processes\_from\_cnf\_staff - ElectronBeamLithography - TrainingMaterials (accessible on any general use PC or CNF Thin client at CNF)

### **SCHEDULING/SIGN-UP RESTRICTIONS**

Minimum Tool Time: 30 minutes

- Please put the beam current you plan to use in the Process field in Coral when you make the reservation.
- No more than 3 hour reservation between the hours of 8am 8pm, Monday through Friday.
- Maximum 12 hours reserved in advance at any time per person.
- The same user, group, or company must have at least 3 hours between any 2 reservations.

#### **MATERIALS COMPATIBILITY CATEGORY**

Tool Category 5: Class A and B Metals and Compounds	
Allowed	Not Allowed
Tool category 1/1E, 2, 3, and 4 materials	
Silicon Based Substrates and Films	
III/V compound Semiconductors	
Glass Substrates	
PECVD and ALD Films	
Cured organics and baked Photoresist	
CNF Class A, B, and Refractory metals	
Exposed Gold, Silver, Copper	
Alkali and Alkaline Compounds	
Organic/Biology Molecules prepared-w/salt buffers	
High Vapor Pressure Materials (Mg, Ca, Zn)*	* Some tool restrictions on high vapor pressure materials may apply
Soft organic materials	

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

### **Additional Material Restrictions and Exceptions**

- Fully baked resists only; do not load samples with unbaked resist or glue or anything that may degas.
- Please review electron beam lithography training materials, in AFS, at shares public processes\_from\_cnf\_staff ElectronBeamLithography TrainingMaterials (accessible on any general use PC or CNF Thin client at CNF)

Last Updated: 03/27/2024